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PATENT APPLICATION
Do. No. 1941-76

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Jun LIU; Karel DOMANSKY; Xiohong LI; Glen E. FRYXELL;
Suresh BASKARAN; Nathan J. KOHLER; and Suntharampillai THEVUTHASAN

Serial No. 09/837,885

Examiner: Leanna Roche

Filed: April 18, 2001

Group Art Unit: 1771

For: MESOPOROUS SILICA FILM FROM A SOLUTION CONTAINING
A SURFACTANT AND METHODS OF MAKING SAME

BOX FEE AMENDMENT
Assistant Commissioner for Patents
Washington, D.C. 20231

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THIRD PRELIMINARY AMENDMENT

Please amend the application as follows, prior to examination of the application on its merits.

IN THE CLAIMS

97 Please add the claims as follows:

24. (New) A dehydroxylated mesoporous silica film prepared from a surfactant containing silica precursor solution, wherein dehydroxylation of the porous film comprises the following steps:
a. exposing said porous film to a silane;
b. removing gas-phase and physisorbed species from said porous film.

88 25. (New) A dehydroxylated mesoporous silica film as recited in claim 24, wherein steps (a) and (b) are performed at least once.

89 26. (New) A dehydroxylated mesoporous silica film as recited in claim 24, wherein said gas-phase species and said physisorbed species are removed from said porous film by applying a vacuum on said porous film.